L Number	Hits	Search Text	DB	Time stamp
1	2	(((ultraviolet or uv) with (neon)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:22
2	21	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:25
3	16	((((post adj (expos$ or develop$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer$7 or photopolymer$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:33
4	3	(((ultraviolet or uv) with (neon)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:36
6	0	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:40
7	11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:46
8	1	((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:49
9	20	((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:54
10	0	(((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:00

11	586	(430/328.ccls. not 430/313.cor.) not ((((ultraviolet or uv) with (neon)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not ((((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:15
12	377	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:40
13	1	((((((resist or photoresist or photopolymer$7) near3 (develop$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3))) and etch$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:43
14	1	((((((resist or photoresist or photopolymer$7) near3 (develop$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3))) and etch$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:44
15	0	(((ultraviolet or uv) with (Ne)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:46
16	102	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:47
17	4	(((ultraviolet or uv) with (Ne)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:56
18	71	((ultraviolet or uv) with (Ne)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:00
19	4	430/313.cor. and 430/328.cxr. and (etch$3 with chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:06

22	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:09
-	2	(("20030003407") or ("20030003683")).PN.	USPAT; US-PGPUB	2003/01/25 17:17
-	25384	(resist or photoresist or photopolymer$7) near3 (develop$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:10
-	1494	((resist or photoresist or photopolymer$7) near3 (develop$3)) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:06
-	38757	(Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:07
-	58	(((resist or photoresist or photopolymer$7) near3 (develop$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:07
-	391	(ultraviolet or uv) with (neon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:10
-	57	((ultraviolet or uv) with (neon)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:11
-	2	(((ultraviolet or uv) with (neon)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:19
-	203	((ultraviolet or uv) with (neon)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:12
-	51	((((resist or photoresist or photopolymer$7) near3 (develop$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3))) and etch$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 15:49
-	1644	(resist or photoresist or photopolymer$7) and ((develop$3) adj20 (ultraviolet or uv))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:12
-	84	((Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3)) and ((resist or photoresist or photopolymer$7) and ((develop$3) adj20 (ultraviolet or uv)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:14
-	583	430/328.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 14:11
-	16	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:25
-	181	(post adj (expos$ or develop$4)) adj20 (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:11
-	49	((post adj (expos$ or develop$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer$7 or photopolymer$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:14

-	21	(((post adj (expos$ or develop$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer$7 or photopolymer$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:30
-	15	((((post adj (expos$ or develop$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer$7 or photopolymer$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:31
-	9	("4751170" | "4931351" | "5407786" | "5427649" | "5486424" | "5688723" | "5707783" | "5877075" | "6190837").PN.	USPAT	2003/02/01 10:33
-	567	430/328.ccls. not 430/313.cor.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 14:36
-	1	(((ultraviolet or uv) with (neon)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:35
-	12	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:39
-	11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:46
-	1	((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:49
-	329	((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 15:31
-	66	((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 16:50
-	15	((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:52

–	51	(((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:00
–	554	(430/328.ccls. not 430/313.cor.) not (((((ultraviolet or uv) with (neon)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not ((((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:11
–	1984	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:39
–	1	((((((resist or photoresist or photopolymer$7) near3 (develop$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3))) and etch$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:43
–	1	((((((resist or photoresist or photopolymer$7) near3 (develop$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link$3 or cur$3 or harden$3))) and etch$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:44
–	304	(ultraviolet or uv) with (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:10
–	0	(((ultraviolet or uv) with (Ne)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:45

-	83	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:46
-	3	(((ultraviolet or uv) with (Ne)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:55
-	1	("6054379").PN.	USPAT; US-PGPUB	2003/02/21 17:30
-	58	((ultraviolet or uv) with (Ne)) and ((cross adj link$3 or cur$3 or harden$3) with (polymer$7 or photopolymer$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:58
-	3	430/313.cor. and 430/328.cxr. and (etch$3 with chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 16:06
-	143	430/313,317.ccls. and (etch$3 with chamber) not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:13
-	101	430/313,317.ccls. and (etch$3 near3 chamber) not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:19
-	2231	(resist or photoresist) same ((ultraviolet or uv) with etch$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:23
-	175	((resist or photoresist) same ((ultraviolet or uv) with etch$3)) and 430/313,317,328.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:22
-	17	(resist or photoresist) same ((ultraviolet or uv) with etch$3 near2 chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:23
-	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT; US-PGPUB	2003/08/21 16:07